



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: *Choi*

Art Unit: 2873

Serial No.: 10/027,873

Examiner: Choi, William C.

Filed: 21 December 2001

Docket No. TI-26153

For: CAPACITIVELY COUPLED MICROMIRROR

AMENDMENT

28 July 2003

Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

MAILING CERTIFICATE UNDER 37 C.F.R. § 1.8(A)	
I hereby certify that the above correspondence is being deposited with the U.S. Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, PO Box 1450, Alexandria, VA, 22313-1450 on the date shown below.	
<i>Choi</i>	<i>28 July 2003</i>
Charles A. Brill	Date

Dear Sir:

In response to the Examiner's Action mailed February 27, 2003, applicant amends as follows:

In the drawings:

Please amend Figure 1 as shown in the attached red-lined copies of the drawings.

In the specification:

Please replace the paragraph beginning at page 9, line 4, with the following rewritten paragraph:

The fabrication of the micromirror will be discussed in reference to Figure 1. A first layer of supports, typically called spacervias, is fabricated on the metal layer forming the bias electrodes 110 and mirror bias connections 112. These spacervias, which include both hinge support spacervias 116 and upper bias electrode spacervias 118, are typically formed by spinning a thin spacer layer over the bias electrodes 110 and mirror bias connections 112. This thin spacer layer is typically a 1 μ m thick layer of positive photoresist. After the photoresist layer is deposited, it is exposed, patterned, and deep UV hardened to form holes in which the spacervias will be formed. This spacer layer and a thicker spacer layer used later in the fabrication process are often called sacrificial layers since they are used only as forms during the fabrication process

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